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Block copolymer thin films with long-range lateral order ILJA GUNKEL, Lawrence Berkeley National Laboratory, TING XU, University of California, Berkeley, ALEXANDER HEXEMER, Lawrence Berkeley National Laboratory, THOMAS RUSSELL, University of Massachusetts, Amherst — We investigated thin block copolymer films on silicon wafers as well as faceted surfaces of sapphire. Thin films were prepared by spin-coating block copolymer solutions on the corresponding substrates. Subsequent annealing in organic solvent vapors served as a means to induce lateral long-range order in the thin films. The resulting block copolymer structures were analyzed by AFM and GISAXS.

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